

Patent Abstracts of Japan

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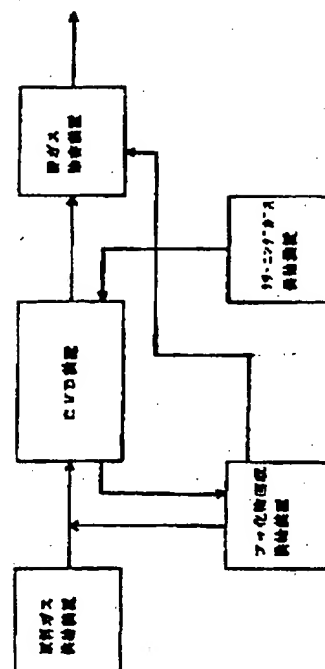
APPLICATION DATE : 10-04-91  
APPLICATION NUMBER : 03077786

APPLICANT : CENTRAL GLASS CO LTD;

INVENTOR : MORI ISAMU;

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TITLE : FILM FORMING DEVICE PROVIDED  
WITH DEPOSIT RECOVERING DEVICE



ABSTRACT : PURPOSE: To highly economically and efficiently perform CVD in the film forming device by CVD using metal fluorides as the raw material by cleaning off the deposit in the CVD device, recovering and reusing the generated fluorides.

CONSTITUTION: The metal fluorides (WF<sub>6</sub>, etc.) as the raw material hydrogen, hydrocarbons, etc., are supplied to a CVD device from a raw gas feeder to form a film, and the fluorides, etc., in the waste gas are absorbed in a waste gas cleaning device. At this time, a cleaning gas feeder is connected to the CVD device through a pipeline, cleaning gases (F<sub>2</sub> gas, ClF<sub>3</sub> gas) are sent to the CVD device or the waste gas cleaning device to clean off the deposit. The deposit is converted to the fluoride by the cleaning gas, and the fluoride is introduced into a fluoride recovering and supplying device, stored and then used as the raw gas.

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